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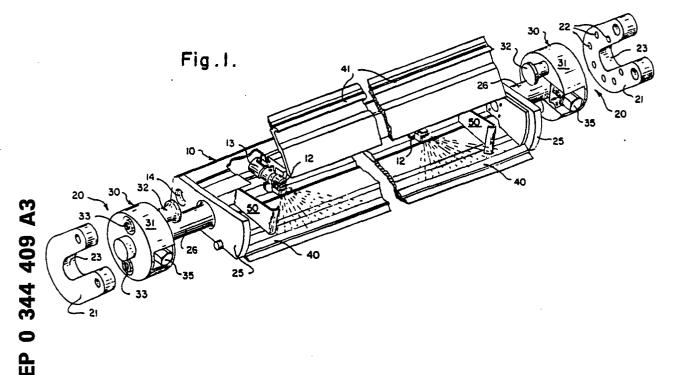
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- 9 Printing press dampener.
- © Spray rail means for use in supplying dampening fluid in an offset lithographic press, the rail including hinged spray shields (40-41) extending

across the width thereof and having improved means for mounting the shields (40-41) on the body (10) of the rail and for mounting the rail on the press frame.



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EUROPEAN SEARCH REPORT

EP 89 10 3760

ategory	Citation of document with in of relevant pa	ndication, where appropriate, ssages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.4)	
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